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PAGE 1

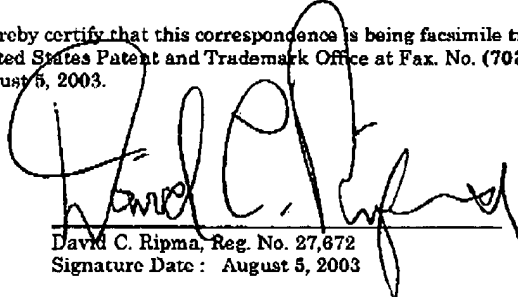
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	)	<u>PATENT APPLICATION</u>
	)	
Inventor: Hirohiko Nishiki, James M. Atkinson, and Yukihiro Nakata	)	August 5, 2003
	)	
Serial No.: 10/040,646	)	ATTORNEY DOCKET
	)	No. SLA0452
	)	
Filed: January 7, 2002	)	Group Art Unit: 1765
	)	
Title: SYSTEM AND METHOD FOR ETCHING RESIN WITH AN OZONE WET PROCESS	)	Examiner: Anita Karen Alanko

# 4  
8/7/03  
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GROUP 1700

CERTIFICATE OF TRANSMITTAL UNDER 37 C.F.R. § 1.8

I hereby certify that this correspondence is being facsimile transmitted to the United States Patent and Trademark Office at Fax. No. (703) 872-9810 on August 5, 2003.

  
David C. Ripma, Reg. No. 27,672  
Signature Date: August 5, 2003

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop Non-Fee Amendment  
Hon. Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This communication responds to an Office Action dated July 30, 2003 in the above-identified patent application.

In the Office Action the Examiner requires restriction to one of the following inventions:

Group I. Claims 1-8 and 20, drawn to a method for cleaning  
a resin residue; and

Group II. Claims 9-19, drawn to a method for repairing a  
resin interlayer surface.

Applicants hereby elect to pursue the Group I claims, claims 1-8  
and 20.

Date: 8/5/03

Respectfully submitted,

By: 

David C. Ripma,  
Reg. No. 27,672

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GROUP I & II